IN THE UNITED STA

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Confirmation No.: 4742

CASTENMILLER et al.

Group Art Unit: 2882

Appln. No.:

09/739,622

Examiner:

Ho, Allen C.

Filed:

December 20, 2000

Title: POSITION DETECTION SYSTEM FOR USE IN LITHOGRAPHIC APPARATUS

November 18, 2002

## AMENDMENT FILED WITH REQUEST FOR CONTINUED EXAMINATION UNDER 37 C.F.R. § 1.114

Hon. Commissioner of Patents Washington, D.C. 20231

Sir:

In reply to the Office Action dated July 18, 2002, and the Advisory Action dated October 8, 2002, the period for reply being extended by a Petition for One-Month Extension of Time filed herewith, prior to examination of the merits in accordance with the Request for Continued Examination filed herewith, please amend the above-identified application as follows:

## IN THE CLAIMS:

Please cancel claim 17 without prejudice or disclaimer.

Please add claims 18-20 as follow:

18. (New) A lithographic projection apparatus comprising:

a projection beam illumination system which supplies a projection beam of radiation;

a first object table for holding a projection beam patterning device which patterns the projection beam according to a desired pattern;

a second object table for holding a substrate; and

a projection system which images the patterned beam onto a target portion of the substrate;

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